

1. A apparatus of manufacturing a semiconductor comprising:

a glass substrate;

a stage having means for flattening and mounting the glass substrate; and

means for irradiating a linear laser beam onto an irradiated surface over the glass substrate while scanning the linear laser beam.

2. A laser annealing apparatus comprising:

a glass substrate;

a stage having a flat surface on which the glass substrate is mounted;

means for contacting a lower surface of the glass substrate with the flat surface of the stage; and

means for irradiating a linear laser beam onto an irradiated surface over the glass substrate while scanning the linear laser beam.

3. A laser annealing apparatus comprising:

a glass substrate having a crystalline silicon film crystallized by heating;

a stage having means for mounting and flattening the glass substrate thereon; and

means for irradiating the linear laser beam on the crystalline silicon film formed on the glass substrate while scanning the linear laser beam.

4. A laser annealing apparatus comprising:
a glass substrate having a crystalline silicon film
crystallized thereon by heating;
a stage having a flat surface on which the glass
substrate is mounted and means for contacting a lower surface
of the glass substrate with the flat surface thereof; and
means for irradiating a linear laser beam onto the
crystalline silicon film while scanning the linear laser beam.

5. A laser annealing apparatus comprising:
a glass substrate having a crystalline silicon film
crystallized thereon by heating;
a stage having a flat surface on which the glass
substrate is mounted and means for making a lower surface of
the glass substrate suck on the flat surface thereof under
vapor; and
means for irradiating the linear laser beam onto the
crystalline silicon film while scanning the linear laser beam.

6. A laser annealing apparatus comprising:
a glass substrate having a crystalline silicon film
crystallized thereon by heating;
a stage having a flat surface on which the glass
substrate is mounted and means for pressing an upper surface
of the glass substrate; and
means for irradiating a linear laser beam onto the
crystalline silicon film while scanning the linear laser beam.

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